

Appl. No. 10/757,802
Reply to Advisor's Action of March 30, 2006

Attorney Docket No. 2002-0350 /24061.484
Customer No. 42717

Amendments To The Claims

Please cancel Claims 15-19 without prejudice. The following list of the claims replaces all prior versions and lists of the claims in this application.

1. (Previously presented) A method for the planarization of an integrated circuit structure comprising:
 - providing a substrate having a plurality of patterned regions;
 - polishing said substrate with an initial chemical mechanical polishing slurry until partial planarization occurs; and
 - continuing to final planarization with a second slurry;wherein said initial slurry comprises a diluted ceria-based slurry with the compositions that ranges from 0.5 wt. % to 1.0 wt. % ceria; and
- wherein said second slurry comprises a ceria-based slurry with composition ranging from 1.0 wt. % to 2.0 wt. % ceria, said initial slurry and said second slurry having different concentrations of ceria.
2. (Original) The method of claim 1 wherein said integrated circuit structure comprises shallow trench isolation.
3. (Original) The method of claim 2 wherein said shallow trench isolation comprises silicon oxide, silicon nitride and polysilicon layers in various configurations.

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4. (Canceled).

5. (Canceled).

4 6. (Original) The method of claim 1 wherein said polishing said substrate with said initial chemical mechanical polishing slurry until partial planarization occurs comprises a control of polishing time so as to avoid overpolishing of a stop layer.

7. (Canceled).

5 8. (Original) The method of claim 1 wherein said continuing to final planarization with said second slurry completes said planarization.

6 9. (Previously presented) A method for the planarization of an integrated circuit structure comprising:

providing a substrate having a plurality of patterned regions wherein said substrate is to be planarized to a stop layer;

polishing said substrate with a first chemical mechanical polishing slurry composition until partial planarization occurs; and

thereafter continuing to final planarization with a second slurry;

wherein said first slurry comprises a diluted ceria-based slurry with compositions ranging from 0.5 wt. % to 1.0 wt. % ceria

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wherein said second slurry comprises a ceria-based slurry with composition ranging from 1.0 wt. % to 2.0 wt. % ceria, said first and second slurries having different concentrations of ceria.

7 10. (Original) The method of claim 9 wherein said integrated circuit structure comprises shallow trench isolation comprising silicon oxide and wherein said stop layer comprises one or more silicon nitride or polysilicon layers.

11. (Canceled).

12. (Canceled).

8 13. (Original) The method of claim 9 wherein said polishing said substrate with said first chemical/mechanical polishing slurry composition until partial planarization occurs further comprises a control of polishing time so as to avoid overpolishing of said stop layer.

14. (Canceled).

15. (Canceled).

15. (Canceled).

17. (Canceled).